

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of	)	
	)	Examiner: Rachuba, Maurina
Xiuhua Zhang	)	
	)	Art Unit: 3723
Application No. 10/743,963	)	
	)	Docket No. LAM2P456
Filed: December 22, 2003	)	
	•	Date: August 24, 2005
For: CHEMICAL MECHANICAL PLANARIZATION	)	
(CMP) SYSTEM AND METHOD FOR PREPARING	)	
A WAFER IN A CLEANING MODULE	)	

**CERTIFICATE OF EXPRESS MAILING** 

I hereby certify that this correspondence is being deposited with the United States Postal Service on August 24, 2005, in an envelope as first class mail, addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

## RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In response to the Restriction Requirement dated July 28, 2005, Applicants hereby elect, without traverse, Group III, Claims 13-21, to prosecute in the above-identified Patent Application.

Should the Examiner have any questions concerning this matter, the undersigned can be reached at the telephone number set out below.

Respectfully submitted,

MARTINE PENILLA & GENCARELLA, LLP

Michael L. Gencarella, Esq.

Reg. No. 44,703

710 Lakeway Drive, Suite 200 Sunnyvale, CA 94085 Telephone (408) 749-6900 Customer No. 25920

Attorney Docket No: LAM2P456